

Supporting Information for

Direct CVD Growth of Graphene/MoS₂ Heterostructure with Interfacial Bonding for Two-Dimensional Electronics

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KEYWORDS

Graphene, Direct growth, Heterostructure, Transition metal dichalcogenides, Contact resistance

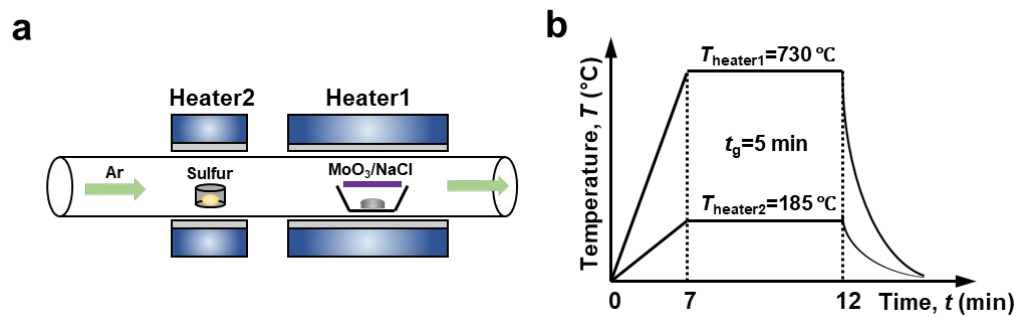


Figure S1. (a) Schematic diagram of the CVD experimental setup (b) and growth condition for MoS₂ synthesis.

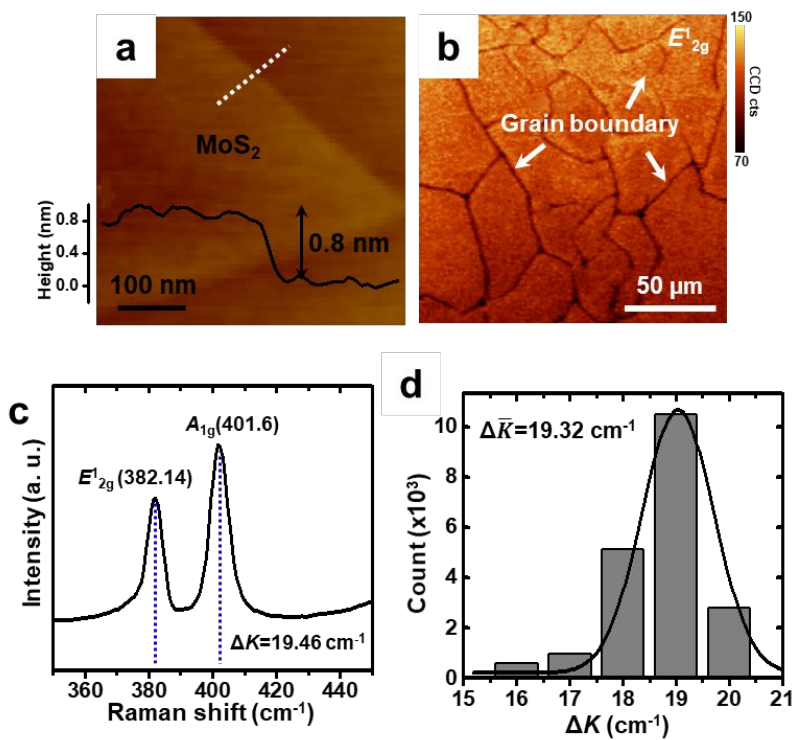


Figure S2. (a) AFM morphology of the MoS₂ monolayer for measuring thickness. (b) E_{12g}^1 Raman mapping data and (c) single Raman spectrum of the synthesized MoS₂ monolayer on SiO₂/Si substrate. (d) The statistics of the Raman peak difference between E_{12g}^1 and A_{1g} peak of the synthesized MoS₂ layer.

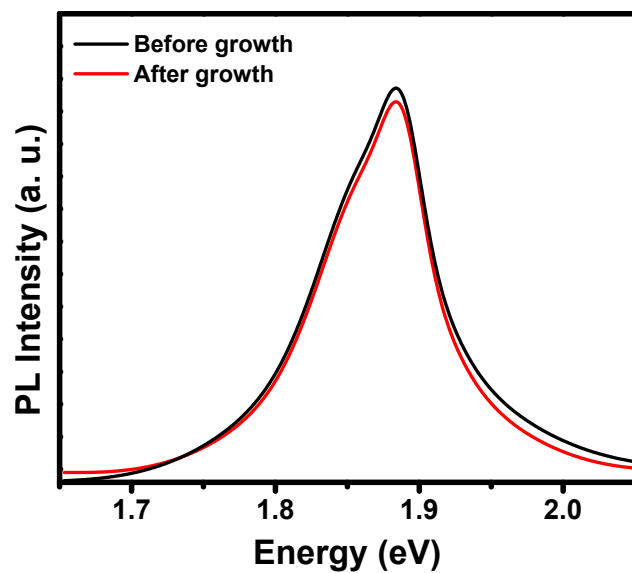


Figure S3. Photoluminescence spectra of the MoS₂ before (black) and after (red) graphene growth at the excitation wavelength of 514 nm.

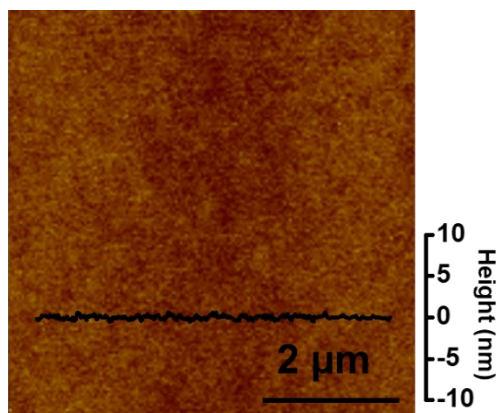


Figure S4. AFM morphology of synthesized graphene/MoS₂ heterostructure.

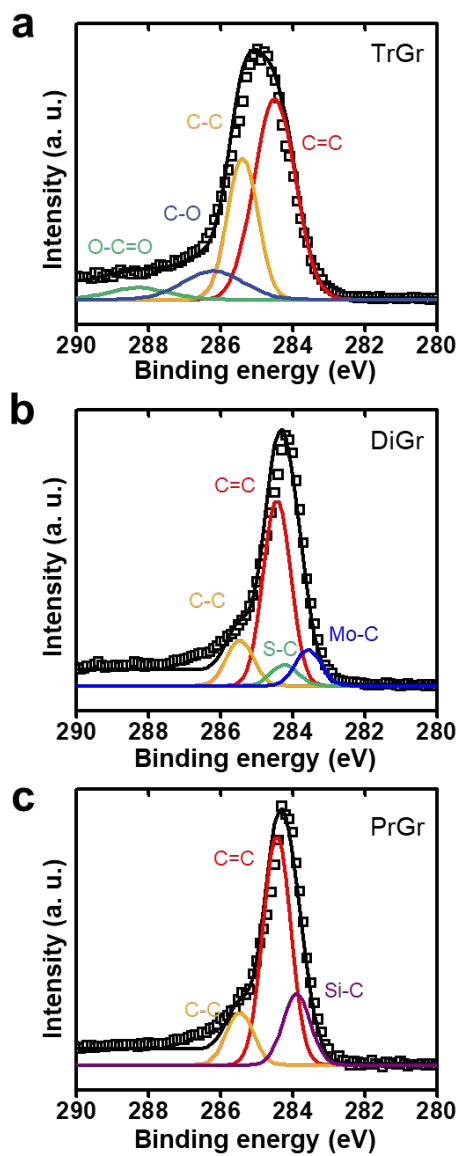


Figure S5. C1s XPS analysis of deconvoluted peaks of the interface between (a) MoS₂/TrGr, (b) MoS₂/DiGr, respectively. (c) C1s XPS analysis of the peak of the directly-grown graphene on SiO₂/Si substrate (PrGr).

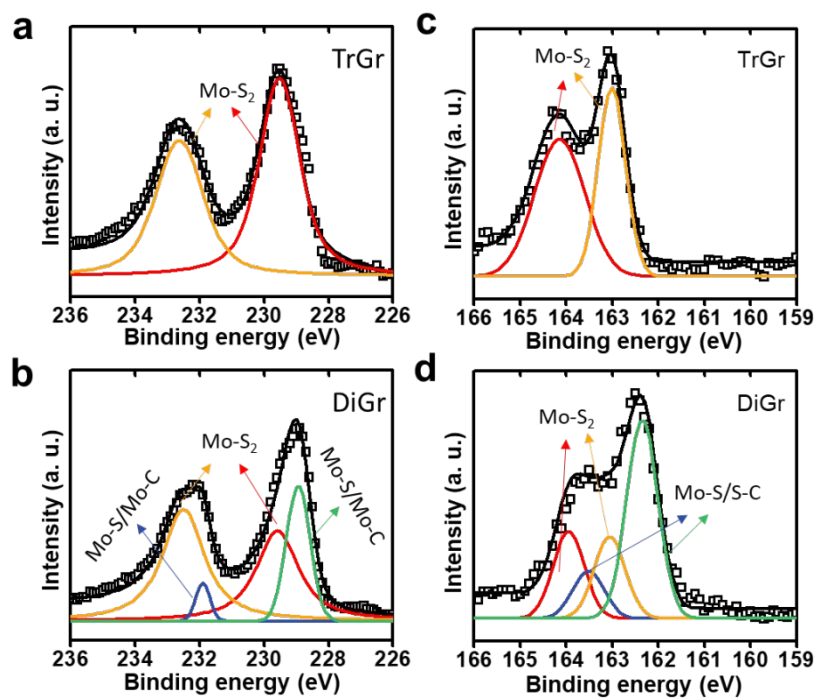


Figure S6. Mo3d XPS analysis of deconvoluted peaks of the interface between (a) MoS₂/TrGr and (b) MoS₂/DiGr. S2p XPS analysis of deconvoluted peaks of the interface between (c) MoS₂/TrGr and (d) MoS₂/DiGr.

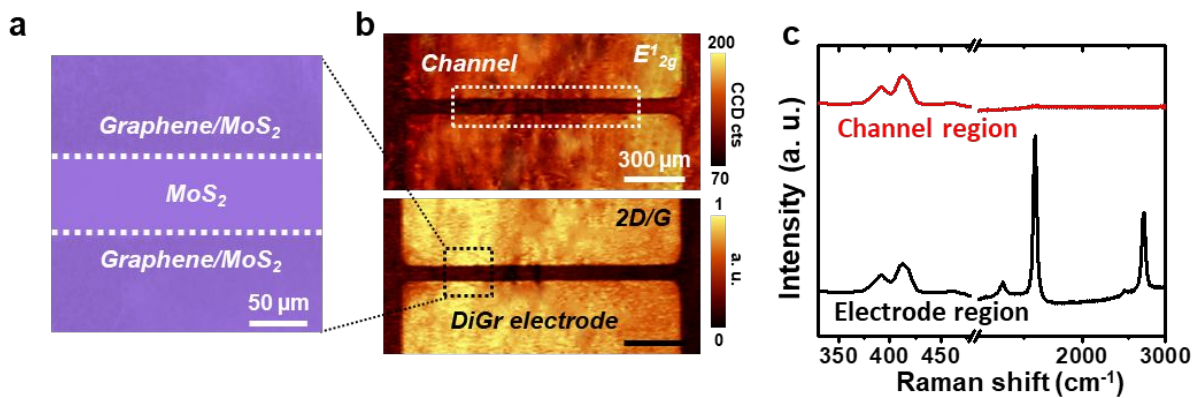


Figure S7. (a) Optical microscopy image of the channel region in the fabricated MoS₂-FETs. (b) (top) E_{12g} and (bottom) $2D/G$ Raman mapping data of directly grown patterned graphene on MoS₂ monolayer. (c) Single Raman spectrum of the channel region (white dashed area) and electrode region.

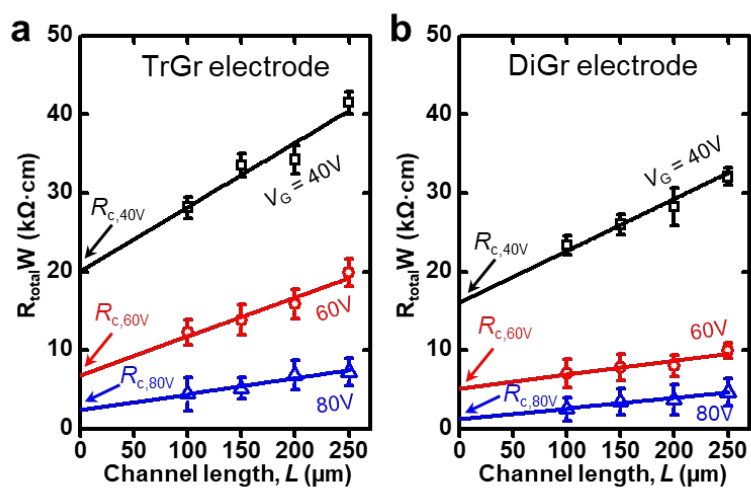


Figure S8. Channel width-normalized R_{total} obtained from the MoS_2 FETs prepared with (a) transferred graphene electrodes (TrGr) and (b) directly-grown graphene electrodes (DiGr) on SiO_2/Si substrate.

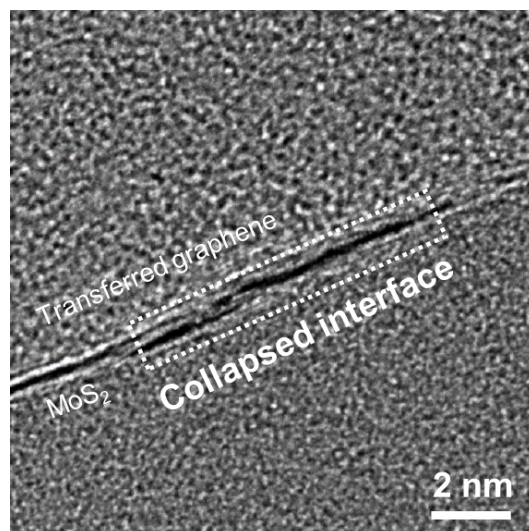


Figure S9. High resolution cross-sectional TEM image of the transferred graphene/MoS₂ monolayer interface on SiO₂/Si substrate.

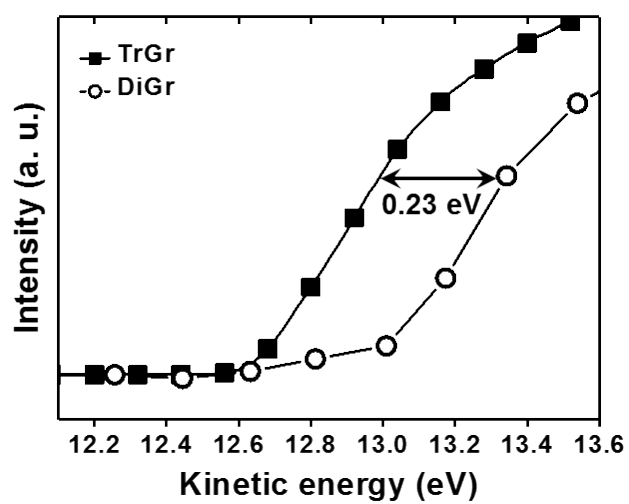


Figure S10. UPS curves obtained from TrGr (closed rectangular) and DiGr (open circle), in the secondary electron emission region.